



Case Docket No. ASMEX.333A Date: April 9, 2002

Page 1

In re application of:

Todd, et al.

App. No.

10/074,564

Filed

February 11, 2002

For

THIN FILMS AND

METHODS OF MAKING

THEM (as amended)

Examiner

Unknown

Art Unit

Unknown

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UNITED STATES PATENT AND TRADEMARK OFFICE P.O. Box 2327

Arlington, VA 22202

Sir:

Transmitted herewith is a Preliminary Amendment in the above-identified application.

The fee has been calculated as shown below:

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	CLAIMS REMAINING AFTER AMENDMENT		HIGHEST NO. PREVIOUSLY PAID FOR		PRESENT EXTRA	Γ	RATE	A.	DDITIONAL FEE
Total Claims	54	_	54	=	0	×	\$18	=	\$0
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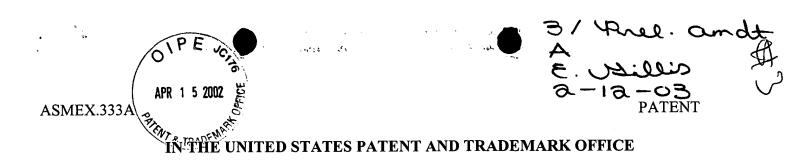
(X) Please charge any additional fees, including any fees for additional extension of time, or credit overpayment to Deposit Account No. 11-1410.

Joseph J. Mallon

Registration No. 39,287

Attorney of Record

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Applicant	:	Todd, et al.) Group Art Unit Unknown
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Filed	:	February 11, 2002	class mail in an envelope addressed to: United States Patent and Trademark Office, P.O. Box 2327, Arlington, VA 22202, on
For	:	THIN FILMS AND METHODS OF MAKING THEM (as amended)) $\frac{9/9/02}{\text{(Date)}}$
Examiner	:	Unknown	Joseph J. Mallon, Reg. No. 39,287

PRELIMINARY AMENDMENT

United States Patent and Trademark Office P.O. Box 2327 Arlington, VA 22202

Dear Sir:

Prior to examination, please amend the above-referenced application as follows:

IN THE TITLE:

Please amend the title to read as follows:

THIN FILMS AND METHOD OF MAKING THEM

IN THE ABSTRACT:

Please replace the Abstract of the Disclosure with the following new Abstract:

Thin, smooth silicon-containing films are prepared by deposition methods that utilize a silicon-containing precursor. In preferred embodiments, the methods result in Si-containing films that are continuous and have a thickness of about 150 Å or less, a surface roughness of about 5 Å rms or less, and a thickness non-uniformity of about 20% or less. Preferred silicon-containing films display a high degree of compositional uniformity when doped or alloyed with other elements. Preferred deposition methods provide improved manufacturing efficiency and